34th International Symposium on Dry Process

DPS 2012

Final Circular

November 15–16, 2012

Takeda Sentanchi Building, The University of Tokyo, Japan

Overview

About DPS

Dry Processes are the state-of-the-art technologies leading the way through ultra-high performance in microelectronic devices. This symposium has provided for more than three decades a valuable forum of discussion on science and technology of new developments in this field.

Theme

Dry processes and related technologies from fundamentals to applications.

Topics

1) Etching Technology
2) Manufacturing Technology(AEC, APC, EES, FDC)
3) Surface Reaction and Damage
4) Plasma Diagnostics and Monitoring System
5) Modeling and Simulation
6) Plasma Generation(Equipment/Source)
7) CVD/PVD/ALD
8) Plasma Processes for 3D Device, FPD, Photovoltaic Devices
9) Plasma Processes for new material devices (MRAM, Power, Organic)
10) Plasma Processes for Biological and Medical Application, MEMS
11) Atmospheric Pressure Plasma and Liquid Plasma
12) New Dry Process Concepts

Arranged Session

A1: Non-Volatile Memory Processes

A2: Plasma Biological Treatment and Medicine

Invited speakers

Dr. Dragan Djurdjanovic (University of Texas at Austin), Dr. Norikatsu Takaura (LEAP),
Dr. Koukou Suu (Ulvac), Dr. Toshiya Hirai (Sony), Dr. Tetsuji Shimizu (Max Planck Institute),
Dr. Toshiaki Kato (Tohoku University), Dr. Hajime Sakakita (AIST)

Registration Fee

Early registration (on or before October 16 2012)

Society member	30,000 JPY
Non-member	35,000 JPY
Student	8,000 JPY

Late registration (on or after October 17 2012)

Society member	35,000 JPY
Non-member	40,000 JPY
Student	10,000 JPY

The registration fee covers participation to all sessions and the conference proceedings with CD-ROM.

Committee Chairpersons

Organizing Committee Chair: Masaru Izawa (Hitachi High-Technologies)
Executive Committee Chair: Takanori Ichiki (The University of Tokyo)
Program Committee Chair: Hikaru Kokura (Fujitsu)
Publication Committee Chair: Seiichiro Higashi (Hiroshima University)

Contact

Symposium Secretariat: Takanori Ichiki, The University of Tokyo
2-11-16 Yayoi, Bunkyo-ku, Tokyo 113-8656 Japan.
E-mail: dps2012@bionano.t.u-tokyo.ac.jp

http://www.dry-process.org/2012/

Sponsors(tentative): DPS 2012 is sponsored by The Japan Society of Applied Physics, in conjunction with The Society of Chemical Engineers, Japan, The Institute of Electrical Engineers of Japan, The Chemical Society of Japan, The Vacuum Society of Japan, The Surface Society of Japan, The Surface Finishing Society of Japan, The Institute of Engineers on Electrical Discharges in Japan, The Institute of Electronics, Information and Communication Engineers of Japan, The Electrochemical Society of Japan, The Japan Society of Plasma Science and Nuclear Fusion Research, and The Center for Advanced Plasma Surface Technology.

応用物理学会プラズマエレクトロニクス分科会の協賛により、11月14日(水)に「第23回プラズマエレクトロニクス講習会」を開催します。

The Japan Society of Applied Physics